Refine Search

Search Results -

Terms	Documents
(hardmask same ((first or second or another) near3 photoresist) same trench).clm.	8

Database:

> US Pre-Grant Publication Full-Text Database
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Search: L3

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Search History

DATE: Wednesday, August 16, 2006   Printable Copy   Create Case

Set Name side by side	Query	Hit Count	Set Name result set
DB=PGPB; PLUR=YES; OP=ADJ			
L3	(hardmask same ((first or second or another) near3 photoresist) same trench).clm.	8	L3
L2	(hardmask same ((first or second or anther) near3 photoresist) same trench).clm.	8	L2
L1	"10603041"	1	L1

END OF SEARCH HISTORY